

Protected: Tutorial Notes

ALD & ALE 2017 Tutorial Schedule and Notes

If you have registered to attend the tutorial the notes will be available in early July. A password will be included in your tutorial registration confirmation letter. Please note that no printed materials will be available onsite so please download in advance.

Saturday, July 15, 2017, 1:00 p.m.-6:00 p.m.

- 1:00-1:05 – Tutorial Welcome
- 1:05-1:50 – David Emslie (McMaster Univ.), “ALD Precursors, Precursor Design, Chemistry and Mechanisms” (PDF)
- 1:50-2:35 – Adrie Mackus (Eindhoven Univ. of Technology), “Approaches, Challenges, and Opportunities for Area-selective ALD” (PDF)
- 2:35-3:20 – Mato Knez (Nanogune), “Coating of Physically and Chemically Challenging Substrates” (PDF)
- 3:20-3:40 – Break
- 3:40-4:25 – Simon Elliott (Tyndall National Institute), “What Theory Can Tell us About ALD Mechanism” (PDF)
- 4:25-5:10 – Vincent Donnelly (University of Houston), “Basic Mechanisms in Plasma Etching” (PDF)
- 5:10-5:55 – Geun Young Yeom (Sungkyunkwan Univ.), “Atomic Layer Etching with Ion/Neutral Beams” (PDF)